



2813

Docket No. 207224US0

IN RE APPLICATION OF: Satoshi KIKUCHI et al

SERIAL NO: 09/846,255

FILED: May 2, 2001

FOR: CLEANING PROCESS FOR SUBSTRATE SURFACE

ASSISTANT COMMISSIONER FOR PATENTS  
WASHINGTON, D.C. 20231

SIR:

Transmitted herewith is an amendment (with marked-up copy) in the above-identified application.

- No additional fee is required
- Small entity status of this application under 37 C.F.R. §1.9 and §1.27 is claimed.
- Additional documents filed herewith:

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The Fee has been calculated as shown below:

CLAIMS	CLAIMS REMAINING		HIGHEST NUMBER PREVIOUSLY PAID	NO. EXTRA CLAIMS	RATE	CALCULATIONS
TOTAL	13	MINUS	20	0	× \$18 =	\$0.00
INDEPENDENT	1	MINUS	3	0	× \$84 =	\$0.00
		<input type="checkbox"/> MULTIPLE DEPENDENT CLAIMS		+ \$280 =		\$0.00
						\$0.00
		<input type="checkbox"/> Reduction by 50% for filing by Small Entity				\$0.00
		<input type="checkbox"/> Recordation of Assignment		+ \$40 =		\$0.00
						TOTAL
						\$0.00

- A check in the amount of \_\_\_\_\_ is attached.
- Please charge any additional Fees for the papers being filed herewith and for which no check is enclosed herewith, or credit any overpayment to deposit Account No. 15-0030. A duplicate copy of this sheet is enclosed.
- If these papers are not considered timely filed by the Patent and Trademark Office, then a petition is hereby made under 37 C.F.R. §1.136, and any additional fees required under 37 C.F.R. §1.136 for any necessary extension of time may be charged to Deposit Account No. 15-0030. A duplicate copy of this sheet is enclosed.

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MAIER & NEUSTADT, P.C.

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Norman F. Oblon  
Registration No. 24,618

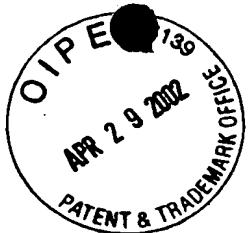
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IN THE UNITED STATES PATENT & TRADEMARK OFFICE

IN RE APPLICATION OF :

SATOSHI KIKUCHI ET AL : EXAMINER: SCHILLINGER, L.

SERIAL NO: 09/846,255 :

FILED: MAY 2, 2001 : GROUP ART UNIT: 2813

FOR: CLEANING PROCESS FOR  
SUBSTRATE SURFACE

AMENDMENT

ASSISTANT COMMISSIONER FOR PATENTS  
WASHINGTON, D.C. 20231

SIR:

Responsive to the Office Action dated January 29, 2002, Applicants respectfully request reconsideration of the above-identified application in view of the following amendment and remarks.

IN THE CLAIMS

Please amend Claim 1 as follows:

- Sub B2*
1. (Amended) A process for cleaning a surface of a substrate, said surface carrying thereon a high-density film and a low-density film lower in density than said high-density film in combination, which comprises continuously bringing a mixed gas of anhydrous hydrogen fluoride gas and a heated inert gas into contact with said surface of said substrate such that at least a portion of said low-density film is removed without impairing said high-density film beyond a tolerance.

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